

ADVANCEMENTS IN HIGH-EFFICIENCY, FAST TRANSITION EDGE SENSORS SPECTROMETER FOR X-RAY SCIENCE



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WHY ? The best of two worlds

- Wavelength-dispersive spectrometers (crystals, gratings)
 - Excellent energy resolution
 - Excellent background rejection



- Energy-dispersive detectors (SDD, Ge)
 - Wide energy range
 - Large solid angle



- "Ultimate" Superconducting Detectors
 - Wide energy span
 - $\Delta E \sim 1 \text{ eV}$
 - Soft to hard x-ray ranges
 - Count rate > 100 kcps



 Transition Edge Sensors are the closest option



THERMAL DETECTORS (I.E., MICRO-CALORIMETERS)

Low temperature is required



Operate at low temperatures ($T \sim 0.1$ K) where C, G and thermodynamic fluctuations are small.



SUPERCONDUCTING TRANSITION EDGE SENSORS

SQUIDs and Time Division Multiplexing

- Each TES in a column is connected to a single SQUID
- SQUIDs in the column are turned on and off in a sequential order
- The entire column is connected to a second stage SQUID
- Very mature technology
- Used at APS and SLAC (soft x-ray detectors)







SUPERCONDUCTING TRANSITION EDGE SENSORS

Time Division Multiplexing



Ullom et al (NIST)



TRANSITION EDGE SENSORS R&D AT APS



CURRENT SYSTEMS LIMITATIONS...

... and the needs of APS

- "State of the art" systems:
 - Array size ~ 250 pixels, challenging to increase it due to the increased heat load
 - $-\sqrt{N}$ noise penalty (TDM)
 - Count rate is limited by cross-talk in the SQUIDs to ~ 10 cps/pixel (TDM)
 - Only for "low energy" < 1 keV
- APS needs:
 - Current array sizes are ok but a path toward much bigger arrays (~ 1000 pixels) is needed
 - Much higher count rates: ~ 100 cps/pixel
 - Strong interest in higher energies: 6 to 20 keV
 - Moderate interest in very high energies: 20 to 100 keV
- APS research approach:
 - Alternative readout technique Microwave SQUID readout from NIST
 - Stopping power without loosing energy resolution Electroplated Bi



MICROWAVE SQUID READOUT



MICROWAVE MUX READOUT FROM NIST

Frequency Division Multiplexing (i.e., microwave mux) – each sensor is simultaneously sampled



B. Mates, et al, Appl. Phys. Lett. 92, 023514 (2008)

- Each TES detector is coupled to a SQUID amplifier and a microwave resonator.
 - The photon absorption in a TES causes a temporary variation in the TES current. This is coupled to the SQUID via the coupling inductance, which amplifies this variation. This then induce a measurable shift in the superconducting resonator frequency, via the inductive coupling between the SQUID and the resonator.
- The TESs are multiplexed in frequency via the corresponding resonator frequency.
- Possible to multiplex ~ 500 TESs with single pair of coax and 4 DC lines.



FLUX RAMP MODULATION **Definition**

- A periodic ramp that sweeps through the multiple quanta in the SQUID is applied.
- If the ramp rate is much higher than the TES current pulse time constant, then these will look like a phase shift in the SQUID response to the ramp.
- The TES current is directly proportional to the induced phase shift in the modulation: ~ 9 μ A/phase period





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11

FLUX RAMP MODULATION Parameters

- Tunable Parameters:
 - Number of oscillations in one flux ramp - N_{OSC}
 - Ramp frequency F_{RAMP}
 - Number of oscillations used in one modulation N_{USED}
- Benchmarks:
 - System Noise Level (SNL) Noise at 1 kHz (i.e. above the cut-off frequency from the TES/shunt resistor and the coupling inductance
 - System Linearity (SL) Residual to a linear fit of the TES normal state branch

The reset at the end of each ramp cause a glitch





6 keV x-ray TES from NIST:

- Mo/Cu, $T_C = 105 \text{ mK}$, $R_{TES} = 8.8 \text{ m}\Omega$ and evaporated Bi absorber.
- R_{SHUNT} = 300 m Ω and *L* = 690 nH.



FLUX RAMP MODULATION

Optimization

- Parameters optimization at F_{RAMP}=10 kHz and $N_{OSC} = 5$:
 - Best SNL is achieved with $N_{USED} \ge 4 SNL \sim$ 5 - 6 μPhi₀/√Hz.
 - Similar results for SL, with a slight advantage in the case N_{USED} = 4 - SL ~ 0.024 Phi₀.
 - A better grounding of the mux chip lower SNL to 3 - 4 μ Phi₀/ \sqrt{Hz} .
- High sampling rate help the pulse reconstruction
- The limited bandwidth of the resonators (~ 300 kHz) limits the achievable modulation rate: F_{RAMP} x N_{osc}.
- To obtain good sampling rate of the TES current (high F_{RAMP}) N_{OSC} must be kept low
- Parameters optimization at F_{RAMP}=100 kHz and $N_{OSC} = 1$:
 - $N_{USED} = 1 SNL \sim 6 7 \mu Phi_0 / \sqrt{Hz}$ and SL \sim 0.039 Phi₀.



- F_{RAMP} =10 kHz and N_{OSC} = 5
- F_{RAMP} =100 kHz and N_{OSC} = 1



ELECTROPLATED BI ABSORBER



BISMUTH ABSORBERS

Why and How

Why Bismuth?

RRR

0.5

- Low heat capacity.
- High stopping power.
- Why Electroplating?
 - Some evaporated Bi films show a low energy tail that affect the ultimate energy resolution.
 - Electroplated films can grow bigger grains which might help with the tail problem,
 - Relatively easy to grow thick absorber for increased stopping power at high energies.

100 nm

60 nm

20 nm

3

2

Grain size (µm)

L. M. Gades, et. al., IEEE Trans. Appl. Supercond., (2017)

Compatible with pre-existing TES designs and processing (Au and Cu seed layers). 1.5

Bismuth grain size varied with thickness. (a) 2 µm thickness showing ~1-2 µm grains (b) ~2-2.5 µm grains. (c) ~2.5-4 µm grains. (d) ~3-5 µm grains.



electroplating)

is minimized the RRR

as expected.

BISMUTH ABSORBERS Application to TES

- Devices with Au, evaporated Bi, and electroplated Bi on the same chip have been fabricated and characterized under different energy photons.
- Spectra from Au and electroplated Bi are similar, with no low-energy tail.





Mn K α : FWHM ~4 eV @ 6 keV

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- The energy resolution is not affected by the Bi.
- The physical mechanism is still unclear but probably due to the much larger grains.

BISMUTH ABSORBERS

Energy resolution





- Energy resolution not affected by the presence of the Electroplated Bi
- Contribution to C negligible (also confirmed by the analysis on the pulses).





BISMUTH ABSORBERS

Open questions and future steps

Better understanding of the physics behind the effect:

- Physical analysis on representative samples in progress.
- The pulses from the three different devices seem identical.
- Possible variation of the tail shape with the energy of the incident photons may shed some light on the physical mechanism (Tatsuno *et al.* J.Low Temp Phys."Absolute energy calibration of x-ray TES ..." 2016).
- Electroplated sample with different grain sizes may lead to different results,
 i.e. nature of the deposition technique vs morphology of the film.
- Limits of the technique: how thick absorbers can be fabricated? (Already achieved 20 μm structures with standard lithography)

NIST gamma-ray spectrometer







CONCLUSIONS

And possible evolutions

- Microwave SQUID multiplexing technology successfully used for the testing and characterization of 6 keV X-ray TESs.
- Noise levels comparable to the standard TDM technology have been achieved.
- Reasonable speeds have been archived with the current mux chip (300 kHz resonators) at a small price in noise, but some synchrotron applications (100 1000 cps/pixel) may require a new generation of broadband mux chips (1 MHz resonators).
- Electroplated Bi absorbers characterized by
 µm size grains have been developed.
- TES testing devices with electroplated Bi absorbers show no sign of low energy tails, unlike the usual evaporated Bi.
- TES testing devices with electroplated Bi absorbers have shown performance comparable to those of the TESs of reference (Au only).
- Very thick absorbers for high energy applications (6 to 20 keV) have been deposited.
- Study of the applicability to very high energies (20 keV to 100 keV) are under way.

THANKS FOR YOUR ATTENTION

